

# EAST Search History (11pp.)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	971	257/208	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 21:07
L2	904	257/211	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 21:07
L3	4809	257/296	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 21:08
L4	6536	((257/208) or (257/211) or (257/296) or (257/301) or (257/304) or (257/311)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/11 21:08
L5	1	4 and (landing adj pad).ti,ab,clm. and passivati\$2 adj (layer film).ti, ab,clm. and (contact plug).ti,ab, clm. and (thickness thick).ti,ab, clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 21:11
S1	5	"733984".ap.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/10 14:01
S2	106	contact adj hole near6 bit adj line. clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/02/16 07:19
S3	55	contact adj hole near6 bit adj line. clm. and contact adj hole.ab,ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/02/16 07:20
S4	2	contact adj hole near6 bit adj line. clm. and contact adj hole.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/02/16 07:25

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S5	32	bit adj line near2 contact adj hole. ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/02/16 08:30
S6	243	contact adj (plug hole) and (bit adj line bitline) and transistor and gate adj stack and "257"/\$9.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 16:49
S7	29	(US-20050026329-\$ or US-20040262671-\$ or US-20040262657-\$ or US-20040206994-\$ or US-20040198007-\$ or US-20040108535-\$ or US-20040036177-\$ or US-20040000717-\$ or US-20030027395-\$ or US-20020135072-\$ or US-20020125508-\$ or US-20020119624-\$ or US-20020098654-\$).did. or (US-6885542-\$ or US-6838737-\$ or US-6806187-\$ or US-6787839-\$ or US-6740923-\$ or US-6682984-\$ or US-6576944-\$ or US-6531350-\$ or US-6459116-\$ or US-6365453-\$ or US-6348709-\$ or US-6333240-\$ or US-6333225-\$ or US-6329263-\$ or US-6043119-\$ or US-5679970-\$).did.	US-PGPUB; USPAT	OR	OFF	2005/07/09 16:44
S8	4365	((257/296) or (257/301) or (257/304) or (257/311) or (257/208) or (257/211)).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/07/09 16:50
S9	50	S8 and (short-circuit short) near4 (contact adj (hole plug))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:49
S10	0	contact adj hole near6 polysicon near3 (liner conformal\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:50
S11	0	contact adj hole near6 polysicon near6 (liner conformal\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:50

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S12	0	contact adj (plug hole) near6 polysicon near6 (liner conformal\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:50
S13	39	(storage adj node contact adj (plug hole)) near6 polysilicon near6 (liner conformal\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:50
S14	39	(storage adj node contact adj (plug hole)) near6 polysilicon near6 (liner conformal\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 18:51
S15	34	(US-20050026329-\$ or US-20040262671-\$ or US-20040262657-\$ or US-20040206994-\$ or US-20040198007-\$ or US-20040108535-\$ or US-20040036177-\$ or US-20040000717-\$ or US-20030027395-\$ or US-20020135072-\$ or US-20020125508-\$ or US-20020119624-\$ or US-20020098654-\$ or US-20050012128-\$ or US-20040201043-\$ or US-20050095857-\$).did. or (US-6885542-\$ or US-6838737-\$ or US-6806187-\$ or US-6787839-\$ or US-6740923-\$ or US-6682984-\$ or US-6576944-\$ or US-6531350-\$ or US-6459116-\$ or US-6365453-\$ or US-6348709-\$ or US-6333240-\$ or US-6333225-\$ or US-6329263-\$ or US-6043119-\$ or US-5679970-\$ or US-6274426-\$ or US-6225214-\$).did.	US-PGPUB; USPAT	OR	OFF	2005/07/09 19:48
S16	2495	(257/296).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/07/09 19:48
S17	1592	S16 and ("poly-Si" polysilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 19:49

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S18	942	S16 and ("poly-Si" polysilicon) and (contact adj hole contact adj plug plug)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 20:03
S19	1505	polysilicon near1 spacer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 20:03
S20	50	polysilicon near1 spacer and contact adj plug and gate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 20:08
S21	50	polysilicon near1 spacer and contact adj plug and gate and polysilicon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 20:53
S22	19	polysilicon near2 spacer and contact adj plug and gate and polysilicon and second adj2 spacer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 20:59
S23	8	polysilicon adj spacer and contact adj plug and gate and polysilicon and second adj2 spacer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:08
S24	9	polysilicon adj spacer and polysilicon and second adj2 spacer and contact adj plug	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:12
S25	115	(polysilicon poly-Si silicon) near1 spacer and second adj2 spacer and contact adj (hole plug)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:13
S26	51	(polysilicon poly-Si silicon) adj spacer and second adj2 spacer and contact adj (hole plug)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:13
S27	11	(polysilicon poly-Si silicon) adj spacer and second adj2 spacer and contact adj (hole plug) and passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:23

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S28	0	(polysilicon poly-Si silicon) adj liner and second adj2 spacer and contact adj (hole plug) and passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:23
S29	1	(polysilicon poly-Si silicon) adj liner and contact adj (hole plug) and passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:24
S30	1	(polysilicon poly-Si silicon) adj liner and contact adj (hole plug) and passivation and liner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:25
S31	23	(polysilicon poly-Si silicon) adj liner and contact adj (hole plug) and liner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:29
S32	0	silicon adj liner same contact adj (hole plug) same passivation adj (film layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:30
S33	4	silicon adj (spacer liner) same contact adj (hole plug) same passivation adj (film layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:38
S34	4	silicon adj (spacer liner) same contact adj (hole plug) same passivation adj (film layer) and (spacer liner)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 21:38
S35	0	polysilicon near2 liner and contact adj (hole plug) and passivation adj (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:02
S36	2078	polysilicon near2 (layer film liner) and contact adj (hole plug) and passivation adj (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:03
S37	1324	polysilicon near2 (sidewall side adj wall film liner) and contact adj (hole plug) and passivation adj (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:03

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S38	1265	polysilicon near2 (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:08
S39	1	polysilicon near2 (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj (layer film) and landing adj pad	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:04
S40	1047	polysilicon near2 (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj film	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:09
S41	999	polysilicon near2 (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj film and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:09
S42	891	polysilicon near1 (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj film and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:09
S43	847	polysilicon adj (sidewall side adj wall film liner) and gate and contact adj (hole plug) and passivation adj film and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:09
S44	133	polysilicon adj (sidewall side adj wall film liner) same contact adj (hole plug) and passivation adj film and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:09
S45	25	polysilicon adj (sidewall side adj wall film liner) same contact adj (hole plug) same passivation adj film and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 14:49
S46	27	thickness near2 landing adj pad	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:10
S47	419	silicon adj nitride near4 gate near6 covered	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:11

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S48	4	silicon adj nitride near4 gate near4 covered same passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:20
S49	387	silicon adj nitride near4 gate near4 covered	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:26
S50	46	ILD near2 silicon adj nitride	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:44
S51	17	liner near2 silicon adj nitride same gate same drain	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:47
S52	0	liner near2 silicon adj nitride same gate same drain same (storage adj node contact adj (plug hole))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:48
S53	6	liner near2 silicon adj nitride same gate same drain and (storage adj node contact adj (plug hole))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/10 15:48
S54	5	"733984".ap.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/05 14:13
S55	1	(US-20040201043-\$).did.	US-PGPUB	OR	OFF	2005/12/05 14:13
S56	1	S55 and (thick thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/05 14:45
S57	2	("5410183").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/05 14:45



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S58	2	("5410183").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/08 21:24
S59	1	(US-20040201043-\$).did.	US-PGPUB	OR	OFF	2006/01/08 21:29
S60	0	("1andinneradjlandingadjpad").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/08 21:29
S61	0	S58 and inner adj landing adj pad	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/08 21:29
S62	0	S58 and inner adj landing adj pad	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 21:29
S63	1	S59 and inner adj landing adj pad	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 21:32
S64	1	S59 and inner adj landing adj pad and transistor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 21:36
S65	1	S59 and inner adj landing adj pad and transistor and passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 21:52
S66	1	S58 and transistor and passivation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 21:52
S67	7	"5410183"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:31



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S68	2	("5410183").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:36
S69	6178	passivation adj layer near4 (silicon \$2oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:37
S70	1528	passivation adj layer near1 (silicon \$2oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:37
S71	299	passivation adj layer near1 (silicon \$2oxide).clm. and "257"/\$7.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:38
S72	222	passivation adj layer near1 (silicon dioxide).clm. and "257"/\$7.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:40
S73	49	passivation adj layer near1 (silicon adj dioxide).clm. and "257"/\$7.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/10 16:40
S74	17279	bit adj line near4 ("via" contact contact adj hole)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 17:42
S75	1003	bit adj line near4 ("via" contact contact adj hole) and passivati\$2 and ("257"/\$7.ccls. "365"/\$7.ccls. "438"/\$7.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 17:44
S76	897	bit adj line near4 (contact contact adj hole) and passivati\$2 and ("257"/\$7.ccls. "365"/\$7.ccls. "438"/\$7.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 17:44
S77	287	bit adj line near4 (contact adj hole) and passivati\$2 and ("257"/\$7.ccls. "365"/\$7.ccls. "438"/\$7.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 17:45

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S78	93	bit adj line near4 (contact adj hole) and passivati\$2 and ("257"/\$7.ccls. "365"/\$7.ccls. "438"/\$7.ccls.) and interconnect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 17:45
S79	75	bit adj line near4 (contact adj hole) and passivati\$2 and ("257"/\$7.ccls. "365"/\$7.ccls. "438"/\$7.ccls.) and interconnect\$3 and @ad<"20030411"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 18:07
S80	153	landing adj pad near3 (diffusion adj region drain source)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 18:07
S81	53	landing adj pad near3 (diffusion adj region drain source) and memory and capacitor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/10 18:09
S82	4116	barrier near4 (silicon adj nitride)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:12
S83	926	barrier near4 (silicon adj nitride) and dram	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:12
S84	226	barrier near4 (silicon adj nitride) and dram and barrier near4 electrode	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:13
S85	41	barrier near4 (silicon adj nitride) and dram and barrier near4 (lower adj electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:15
S86	26	dram and barrier near8 (lower adj electrode) near8 (silicon adj nitride)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:32
S87	24	(capacitor dram) and barrier near8 (lower adj electrode) near8 (silicon adj nitride) and ("257"/\$7.ccls. "438"/\$7.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 18:33

## EAST Search History

S88	11	"6100138"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 19:11
S89	2	("6100138").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/11 19:12
S90	1	S89 and (thick thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/11 19:12